

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Jyun IWASHITA et al.

Serial No. NEW : **Attn: APPLICATION BRANCH**

Filed March 25, 2004 : Attorney Docket No. 2004_0468A

NEGATIVE RESIST MATERIAL AND
METHOD FOR FORMING RESIST PATTERN

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

Pursuant to the provisions of 37 CFR 1.56, 1.97 and 1.98, Applicants request consideration of the references listed on attached form PTO-1449.

A legible copy of each reference listed on the form PTO-1449 and each U.S. patent application listed below is enclosed.

1a. This Information Disclosure Statement is submitted:

within three months of the filing date (or of entry into the National Stage) of the above-entitled application, or

before the mailing date of the first Office Action on the merits,

and thus no certification and/or fee is required.

1b. This Information Disclosure Statement is submitted

after the events of above paragraph 1a and prior to the mailing date of a final Office Action or a Notice of Allowance or an action which otherwise closes prosecution in the application, and thus:

- (1) the certification of paragraph 2 below is provided, **or**
- (2) the fee of \$180.00 specified in 37 CFR 1.17(p) is enclosed.

1c. This Information Disclosure Statement is submitted:

after the mailing date of a final Office Action or Notice of Allowance or action which otherwise closes prosecution in the application, and prior to payment of the issue fee, and thus:

the certification of paragraph 2 below is provided, and

the fee of \$180.00 specified in 37 CFR 1.17(p) is enclosed.

2. It is hereby certified

- a. that each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the Statement, or
- b. that no item of information contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application and, to the knowledge of the person signing the certification after making reasonable inquiry, was known to any individual designated in §1.56(c) more than three months prior to the filing of the Statement.

3. Consideration of the following list of additional information (including any copending or abandoned U.S. application, prior uses and/or sales, etc.) is requested.

4. For each non-English language reference listed on the attached form PTO-1449, reference is made to:

- a. a full or partial English language translation submitted herewith,

- b. a foreign patent office search report (in the English language) submitted herewith,
- c. the concise explanation contained in the specification of the present application at page ,
- d. the concise explanation set forth in the attached English language abstract,
- e. the concise explanation set forth below or on a separate sheet attached to the reference: See attached sheet.

5. A foreign patent office search report citing one or more of the references is enclosed.

Respectfully submitted,

Jyun IWASHITA et al.

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March 25, 2004

FORM PTO 1449 (modified)

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICELIST OF REFERENCES CITED BY APPLICANT(S)
(Use several sheets if necessary)

Date Submitted to PTO: March 25, 2004

ATTY DOCKET NO.
2004_0468ASERIAL NO.
NEWAPPLICANT
Jyun IWASHITA et al.FILING DATE
March 25, 2004

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	AF	0 232 972	9/1993	Europe			
	AG	8-3635	1/1996	Japan			yes
	AH	2001-174993	6/2001	Japan			abstract
	AI	2002-278069	9/2002	Japan			abstract
	AJ	2002-371114	12/2002	Japan			abstract
	AK	2000-206694	7/2000	Japan			abstract
	AL	8-259626	10/1996	Japan			abstract
	AM						

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

	AN	Tsuchiya, Y. et al., Journal of Photopolymer Science and Technology; Vol. 10, No. 4, pp. 579-584, (1997)
	AO	Maeda, K. et al., Journal of Photopolymer Science and Technology; Vol. 11, No.. 3, pp. 507-512, (1999).
	AP	Iwasa, S. et al., SPIE Advance in Resist Technology and Processing, Vol. 3333, pp. 417-424, (1998).

EXAMINER

DATE CONSIDERED

Country, Application/Publication/Patent Number, Author, Title Name of Document	Issue Date (Application Date)	Concise Explanation of the Relevance (indication of page, column, line, figure of the relevant portion)
1. Japan No. HEI 8-3635 B	Jan. 17, 1996	Equivalent to EP 0 232 972 B1, issued on Sep. 8, 1993
2. Japan No. 2001-174993 A	June 29, 2001	English abstract
3. Journal of Photopolymer Science and Technology, Vol. 10, No. 4 (1997), p. 579-584	1997	
4. Journal of Photopolymer Science and Technology, Vol. 11, No. 8 (1998), p. 579-584	1998	
5. SPIE Advance in Resist Technology and Processing XIV, Vol. 3333, p. 417-424	1998	
6. Japan No. 2002-278069 A	Sep. 27, 2002	English Abstract
7. Japan No. 2002-371114 A	Dec. 26, 2002	English Abstract
8. Japan No. 2000-206694 A	Jul. 28, 2000	English Abstract
9. Japan No. HEI 8-259626 A	Oct. 8, 1996	English Abstract